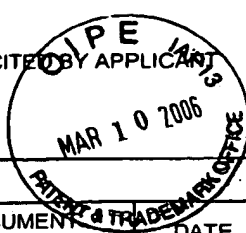


Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 278727US2PCT		SERIAL NO. 10/550,413	
LIST OF REFERENCES CITED BY APPLICANT 				APPLICANT Toshihisa TOMIE		GROUP 2881	
				FILING DATE September 23, 2005			
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						
<b>FOREIGN PATENT DOCUMENTS</b>							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO		
/M.S./	AO	2000-215998	08/04/00	JP (with English abstract & Computer generated translation)		NO	
/M.S./	AP	2000-91095	03/31/00	JP (with English abstract & Computer generated translation)		NO	
/M.S./	AQ	11-250842	09/17/99	JP (with English abstract & Computer generated translation)		NO	
	AR						
<b>OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)</b>							
/M.S./	AS	SUGAR, Jack: "Potential-Barrier Effects in Photoabsorption. II. Interpretation of Photoabsorption Resonances in Lanthanide Metals at the 4d-Electron Threshold", Physical Review B, Vol. 5, No. 5, Pages 1785 -1792, 1972					
/M.S./	AT	O'SULLIVAN, G. et al: "4d-4f emission resonances in laser-produced plasmas", Journal of Optical Society of America, Vol. 71, No. 3, Pages 227 - 230, 1981.					
/M.S./	AU	BENDER, H.A. et al.: "Velocity characterization of particulate debris from laser-produced plasmas used for extreme-ultraviolet lithography", Applied Optics, Vol. 34, No. 28, Pages 6513 - 6521, 1995.					
/M.S./	AV	"Theoretical consideration on power limit of EUV source", National Institute of Advanced Industrial Science and Technology, AIST01-A00007, Ver. 1.1. Pages 1 - 30, 2002. (with partial English translation)					
/M.S./	AW	SCHWENN, U. et al.: "A Continuous droplet source for plasma production with pulse laser", Journal of Physics E: Scientific Instruments, Vol. 7, Page 715 - 718, 1974.					
/M.S./	AX	RYMELL, L. et al.: "Droplet target for low-debris laser-plasma soft X-ray generation", Optics Communications, Vol. 103, No. 1 - 2, Pages 105 - 110, 1993.					
/M.S./	AY	EICKMANS, Johannes H. et al.: "Plasma spectroscopy H, Li, and Na in plumes resulting from laser-induced droplet explosion", Applied Optics, Vol. 26, No. 17, Pages 3721 - 3725, 1987					
/M.S./	AZ	TOMPKINS, R.J. et al.: "5-20 keV laser-induced x-ray generation at 1 kHz from a liquid-jet target", Review of Scientific Instruments, Vol. 69, No. 9, Pages 3113 - 3117, 1998.				<input type="checkbox"/> Additional References sheet(s) attached	
Examiner /Meenakshi Sahu/							
						Date Considered 01/17/2008	
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

Form PTO 1449  
(Modified)U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEATTY DOCKET NO.  
278727US2PCTSERIAL NO.  
10/550,413

## LIST OF REFERENCES CITED BY APPLICANT

APPLICANT  
Toshihisa TOMIEFILING DATE  
September 23, 2005GROUP  
2881

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						

## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
/M.S./	AO	2002/46839	06/13/02	WO		NO
/M.S./	AP	2000-215998	08/04/00	JP		NO
/M.S./	AQ	2000-91095	03/31/00	JP		NO
	AR					
	AS					
	AT					
	AU					
	AV					

## OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

	AW	
	AX	
	AY	
	AZ	

☐ Additional References sheet(s) attached

Examiner /Meenakshi Sahu/

Date Considered 01/17/2008

\*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.